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PRE-APPEAL BRIEF REQUEST FOR REVIEW		Docket Number (Optional) 5347-223	
I hereby certify that this correspondence is being transmitted electronically to the U.S. Patent and Trademark Office	Application N		Filed 02/24/2004
on May 29, 2007 Signature	First Named Inventor  Jeffry A. Kelber  Art Unit   Examiner		
Typed or printed Carey Gregory	2841		Tuan T. Dinh
Applicant requests review of the final rejection in the above-identified application. No amendments are being filed with this request.  This request is being filed with a notice of appeal.			
The review is requested for the reason(s) stated on the attached sheet(s). Note: No more than five (5) pages may be provided.			
I am the applicant/inventor.	A		gnature
assignee of record of the entire interest. See 37 CFR 3.71. Statement under 37 CFR 3.73(b) is enclosed. (Form PTO/SB/96)	Laura M. Kelley  Typed or printed name		
x attorney or agent of record. 48,441  Registration number	919-854-1400		
	Telephone number		
attorney or agent acting under 37 CFR 1.34.  Registration number if acting under 37 CFR 1.34	May 29, 2007  Date		
NOTE: Signatures of all the inventors or assignees of record of the entire interest or their representative(s) are required.  Submit multiple forms if more than one signature is required, see below*.			

This collection of information is required by 35 U.S.C. 132. The information is required to obtain or retain a benefit by the public which is to file (and by the USPTO to process) an application. Confidentiality is governed by 35 U.S.C. 122 and 37 CFR 1.11, 1.14 and 41.6. This collection is estimated to take 12 minutes to complete, including gathering, preparing, and submitting the completed application form to the USPTO. Time will vary depending upon the individual case. Any comments on the amount of time you require to complete this form and/or suggestions for reducing this burden, should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, U.S. Department of Commerce, P.O. Box 1450, Alexandria, VA 22313-1450. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Mail Stop AF, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

### IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re: Jeffry A. Kelber et al. Examiner: Tuan T. Dinh Serial No.: 10/785,615 Group Art No.: 2841

Filed: February 24, 2004 Confirmation No.: 2942 For: CONDUCTORS CREATED BY METAL DEPOSITION USING A

SELECTIVE PASSIVATION LAYER AND RELATED METHODS

May 29, 2007

Mail Stop AF Commissioner for Patents Box 1450 Alexandria, VA 22313-1450

# REASONS IN SUPPORT OF APPLICANTS' PRE-APPEAL BRIEF REQUEST FOR REVIEW

Sir:

This document is submitted in support of the Pre-Appeal Brief Request for Review filed concurrently with a Notice of Appeal in compliance with 37 C.F.R. 41.31 and with the rules set out in the OG of July 12, 2005 for the New Appeal Brief Conference Pilot Program.

It is not believed that an extension of time and/or any additional fee(s) are required beyond those that may otherwise be provided for in documents accompanying this paper. In the event, however, that an extension of time is necessary to allow consideration of this paper, such an extension is hereby petitioned under 37 C.F.R. §1.136(a). Any additional fees believed to be due in connection with this paper may be charged to our Deposit Account No. 50-0220.

#### REMARKS

Applicants hereby request a Pre-Appeal Brief Review (hereinafter "Request") of Claims 28-32, which were finally rejected under § 102(e) as being anticipated by U.S. Patent No. 6,800,542 to Kim ("Kim") and of Claims 33-36, which were finally rejected under § 102(e) as being anticipated by U.S. Patent Publication No. 2005/0124154 to Park et al. ("Park') in the Final Office Action of February 26, 2007 (the "Final Action"). Applicants respectfully submit that the recitations of the claims

In re: Jeffry A. Kelber et al. Serial No.: 10/785,615 Filed: February 24, 2004

Page 2 of 5

are not described or suggested by Kim or Park. Therefore, one or more elements needed for a *prima facie* rejection under 35 USC §102(e) are, therefore, simply not present. Therefore, Applicants respectfully request review of the present application by an appeal conference prior to the filing of an Appeal Brief. In the interest of brevity, and without waiving the right to argue additional grounds should this Request be denied, Applicants will merely point out the Examiner's omissions of one or more essential elements needed for a *prima facie* rejection.

# Claims 28-32 are not anticipated by Kim

Claim 28 recites a conductive structure including:

a first conductor;

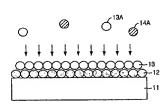
a plurality of atomic layers of a second conductor directly on the first conductor; and

a first solid material directly on the plurality of atomic layers of the second conductor, remote from the first conductor, the first material being penetrable by the plurality of atomic layers of the second conductor relative to at least a second material other than the second conductor.

Applicants submit that Kim does not disclose at least the underlined portion of independent Claim 28. The Final Action on page 2 identifies the materials 13A and 14A as equivalent to the first solid material. However, the materials 13A and 14B are clearly described by Kim as being a gaseous material and not a solid as recited in Claim 28. In particular, column 3, lines 47-55 of Kim refers to Figure 1B (reproduced below) as follows:

As shown in **FIG. 1B**, hydrazine  $(N_2H_4)$  13, which is a reaction gas, is injected ... and ... is reacted with Ru precursor 12 absorbed on the surface of the substrate 11 so that the Ru and volatile byproducts, such as HX, NH<sub>3</sub> and N<sub>2</sub> are produced.... [T]he purge gas is injected again in order to remove the volatile by products 14A and a non-reacted hydrazine 13A and a highly pure Ru thin layer is finally deposited.

FIG. 1B



In re: Jeffry A. Kelber et al. Serial No.: 10/785,615 Filed: February 24, 2004

Page 3 of 5

Therefore, the components 13A, 14A, which the Action identifies as the first solid material, are clearly a gas and not a solid as recited in Claim 28.

In addition, the components 13A, 14A are not <u>directly</u> on the layer 13 (which the Final Action identifies as the plurality of atomic layers of the second conductor). Figure 1B clearly illustrates <u>a gap</u> between the components 13A, 14A and the layer 13.

Therefore, Kim does not teach or suggest at least a first solid material directly on the plurality of atomic layers of the second conductor. Claim 28 is patentable for at least these reasons. Claims 29-32 are patentable at least as depending from patentable Claim 28.

# Claims 33-36 are not anticipated by Park

Claim 33 recites a conductive structure including:

a first layer comprising ruthenium;
a second layer comprising a plurality of atomic layers of
copper directly on the first layer comprising ruthenium; and
a third layer comprising iodine directly on the second layer
comprising a plurality of atomic layers of copper, remote from the first
layer comprising ruthenium.

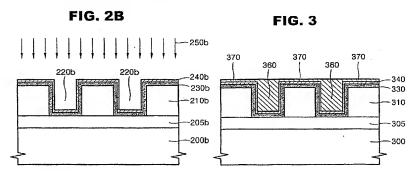
Applicants submit that Park does not disclose various recitations of Claim 33. The Action takes the position that the barrier layer 330 is the "first layer comprising ruthenium" the adhesion layer 340 is the "second layer comprising a plurality of atomic layers of copper," and the layer 370 is the "third layer comprising iodine." *See* the Action, page 3.

Park discusses that the barrier layer 330 may be formed of ruthenium. See Park, paragraph 22. However, Park proposes various materials that could be used as the adhesion layer 340 (also labeled 240a/240b), but does not discuss copper. See paragraph 25 (discussing various materials for the adhesion layer, e.g., ruthenium, rhenium, nickel, palladium, osmium, iridium and platinum, tantalum, tantalum alloys, titanium, titanium alloys, tungsten and tungsten alloys). Therefore, the adhesion layer 340 does not meet the recitation of a "second layer comprising a plurality of atomic layers of copper" in Claim 33 as maintained in the Final Action.

In re: Jeffry A. Kelber et al. Serial No.: 10/785,615 Filed: February 24, 2004

Page 4 of 5

Applicants note that the layer 360 in Park is described as a copper layer, and the catalyst 250b is identified as iodine. See Park, paragraphs 29-30. However, the layer 360 is not "directly on the first layer comprising ruthenium" as recited in Claim 33 because the adhesion layer 340 in Park is between the ruthenium barrier layer 330 and the copper layer 360. Therefore, the layer 360 also does not meet the recitation in Claim 33 of "a second layer comprising a plurality of atomic layers of copper directly on the first layer comprising ruthenium."



In response to Applicants' arguments with respect to layer 360, the Final Action states on page 4 that Applicants recite "a third layer comprising iodine directly on the second layer [comprising a plurality of layers of copper, remote from the first layer comprising ruthenium]." To the extent that the Final Action is taking the position that the layer 360 is equivalent to "a third layer comprising iodine," the layer 360/370 is described by Park as a copper layer 360/370. Therefore, the copper layer 360/370 also does not meet the recitation of a third layer comprising iodine.

In addition, Applicants note that the iodine catalyst 250b that is referred to in Park is not directly on a copper layer (such as the copper layer 360/370) and is also not remote from layers 230/330 or 240/340 (which the Final Action identifies as equivalent to the first layer comprising ruthenium and the second layer comprising a plurality of atomic layers of copper, respectively). Park discusses depositing a copper layer with an iodine or iodine compound as a catalyst in paragraph 13. However, as shown in Figures 2B and 3, the iodine catalyst 250b is deposited before the copper layer 360/370 so that it is not remote from layers 230/330 or 240/340. As noted in Park in paragraphs 29-30 (emphasis added):

[A] semiconductor substrate 200b, on which an adhesion layer 240b is preformed, is treated with iodine or iodine compound as a catalyst 250b.

In re: Jeffry A. Kelber et al. Serial No.: 10/785,615 Filed: February 24, 2004

Page 5 of 5

Referring to **FIG. 3** subsequently, a copper layer **360** is formed using (hfac)Cu(vtms) as a copper precursor on the surface of an adhesion layer **340** by using said chemical vapor deposition method.

Therefore, Park also does not meet the recitation of a "third layer comprising iodine directly on the second layer comprising a plurality of atomic layers of copper, remote from the first layer comprising ruthenium" in Claim 33.

Applicants submit that Claim 33 is patentable for at least the reasons discussed above. Claims 34-36 are patentable at least as depending from patentable Claim 33.

Accordingly, for at least the reasons discussed above, the recitations of the independent Claim 28 are not described or suggested by Kim and the recitations of the independent Claim 33 are not described or suggested by Park so that one or more elements needed for a *prima facie* rejection under 35 USC §102(e) are simply not present. Therefore, Applicants respectfully request Pre-Appeal Brief Review of the present application and that the rejections be reversed by the Pre-Appeal Brief Review Panel prior to the filing of an Appeal Brief.

Respectfully submitted,

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# CERTIFICATION OF ELECTRONIC TRANSMISSION UNDER 37 CFR § 1.8

I hereby certify that this correspondence is being transmitted electronically to the U.S. Patent and Trademark Office on May 29, 2007.

Carey Gregory

Date of Signature: May 29 2007